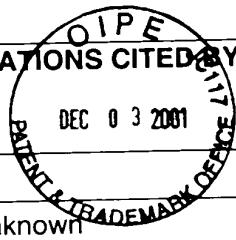


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Examiner <i>MMR</i>	Unknown		

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	A2	4,028,155	06-07-1977	Jacob	156	643	08-10-1976
	A3	4,262,631	04-21-1981	Kibacki	118	723	10-01-1979
	A4	4,308,089	12-29-1981	Iida et al.	156	643	05-09-1980
	A5	4,420,386	12-13-1983	White	204	192	04-22-1983
	A6	4,532,150	07-30-1985	Endo et al.	427	39	12-22-1983
	A7	4,634,601	01-06-1987	Hamakawa et al.	427	39	03-26-1985
	A8	4,711,698	12-08-1987	Douglas	156	643	07-15-1985
	A9	4,759,947	07-26-1988	Ishihara et al.	427	38	10-07-1985
	A10	4,872,947	10-10-1989	Wang et al.	156	643	10-26-1988
	A11	4,895,734	01-23-1990	Yoshida et al.	427	38	03-30-1988
	A12	4,951,601	08-28-1990	Maydan et al.	118	719	06-23-1989
<i>MMR</i>	A13	4,980,196	12-25-1990	Yasuda et al.	427	38	02-14-1990

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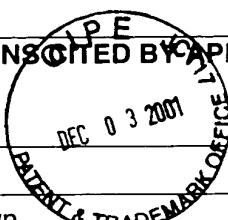
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	B2	DE 19751785A1	05-28-1998	GERMANY	HO1L	21/768	<input type="checkbox"/>	<input checked="" type="checkbox"/>
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	A15	5,000,113	03-19-1991	Wang et al.	118	723	12-19-1986
	A16	5,000,819	03-19-1991	Pedder et al.	156	643	11-29-1989
	A17	5,011,706	04-30-1991	Tarhay et al.	427	39	04-12-1989
	A19	5,043,299	08-27-1991	Chang et al.	437	192	12-01-1989
	A20	5,086,014	02-04-1992	Miyata et al.	437	103	09-18-1990
	A21	5,121,706	06-16-1992	Nichols et al.	118	719	09-21-1990
	A22	5,232,871	08-03-1993	Ho	437	190	06-03-1992
	A23	5,232,872	08-03-1993	Ohba	437	192	03-05-1992
	A24	5,238,866	08-24-1993	Bolz et al.	437	100	09-11-1991
<i>MCL</i>	A25	5,248,636	09-28-1993	Davis et al.	437	225	06-02-1992
<i>MCL</i>	A26	5,266,154	11-30-1993	Tatsumi	156	643	04-27-1992

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<i>MCL</i>	B5	EP 0553961A2	08-04-1993	EUROPE	HO1L	21/311	<input checked="" type="checkbox"/>	<input type="checkbox"/>
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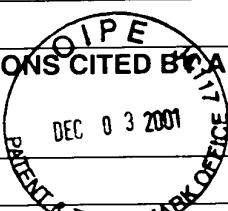
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<i>MCL</i>	C4	Takashi Ito, Takao Nozaki, and Hajime Ishikawa, "Direct Thermal Nitridation of Silicon Dioxide Films in Anhydrous Ammonia Gas," J. Electrochem. Soc., Vol. 127, No. 9, pp. 2053-2057

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	A28	5,401,613	03-28-1995	Brewer et al.	430	323	02-12-1992
	A29	5,409,543	04-25-1995	Panitz et al.	134	2	12-22-1992
	A30	5,423,941	06-13-1995	Komura et al.	156	643.1	11-17-1993
	A31	5,424,246	06-13-1995	Matsuo et al.	437	192	07-30-1993
	A32	5,427,621	06-27-1995	Gupta	134	1	10-29-1993
	A33	5,451,263	09-19-1995	Linn et al.	134	1.1	02-03-1994
	A34	5,458,907	10-17-1995	Ishido	427	96	02-07-1994
	A35	5,465,680	11-14-1995	Loboda	117	84	07-01-1993
<i>V</i>	A36	5,468,978	11-21-1995	Dowben	257	258	07-07-1993
<i>MHC</i>	A37	5,476,182	12-19-1995	Ishizuka et al.	216	68	09-08-1993

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	B11	EP 0725440 A2	08/07/1996	EUROPE	H01L	23/532	X	
	B12	EP 0416400 A1	03-13-1991	EUROPE	C23C	16/44	X	
<i>V</i>	B13	WO 93/17453	09-02-1993	PCT International	H01L	21/306		
<i>MHC</i>	B14	2 775 986	09-17-1999	FRANCE	C23F	1/12		X

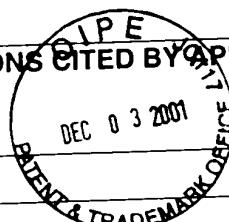
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	A39	5,527,718	06-18-1996	Seita et al.	437	11	12-28-1994
	A40	5,531,862	07/02/1996	Otsubo et al.	156	643.1	07-19-1994
	A41	5,545,592	08-13-1996	Iacoponi	437	200	02-24-1995
	A42	5,565,084	10-15-1996	Lee et al.	205	646	06-07-1995
	A43	5,572,072	11-05-1996	Lee	257	751	11-16-1994
	A44	5,591,566	01-01-1997	Ogawa	430	325	06-07-1995
	A45	5,607,542	03-04-1997	Wu, et al.	156	643.1	11-01-1994
	A46	5,627,105	05-06-1997	Delfino et al.	438	627	04-08-1993
	A47	5,641,607	06-24-1997	Ogawa et al.	430	272.1	09-28-1995
<i>MGL</i>	A48	5,643,834	07-01-1997	Harada, et al.	437	210	05-25-1995

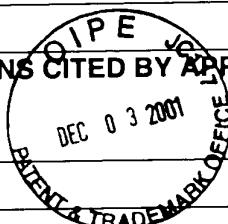
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	B16	197 02 124 A1	07-23-1998	DE	B01J	19/08		X
	B17	JP11-16912	01/22/1999	JP (Abstract)	438	115	X	<input type="checkbox"/>
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	C8	Research Disclosure XP000099373, "Low Temperature Process for Surface Cleaning", No. 309, page 82, 1 January 1990		
<i>MGL</i>	C9	S. Hymes, et al. "Surface Cleaning of Copper by Thermal and Plasma Treatment in Reducing and Inert Ambients", 1 Vac. Sci. Technol. Vol 16, No. 3 May/June 1998; pages 1107-1109		
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	A50	5,674,373	10-17-1997	Negrerie, et al.	205	160	07-11-1994
	A51	5,658,834	08-19-1997	Dowben	438	478	11-17-1995
	A52	5,691,209	11-25-1997	Liberkowski	437	7	10-15-1996
	A53	5,710,067	01-20-1998	Foote et al.	437	238	06-07-1995
	A54	5,711,987	01-27-1998	Bearinger et al.	427	7	10-04-1996
	A55	5,725,938	03-10-1998	Jin, et al.	428	210	08-29-1996
	A56	5,726,097	03-10-1998	Yanagida	438	622	07-25-1995
	A57	5,730,792	03-24-1998	Camilletti et al.	106	287.14	10-04-1996
<i>C</i>	A58	5,736,002	04-07-1998	Allen et al.	156	628.1	08-22-1994
<i>MHC</i>	A59	5,741,626	04-21-1998	Jain et al.	430	314	04-15-1996

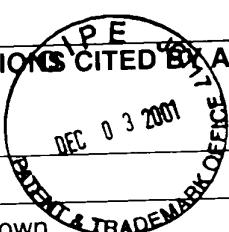
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<i>MHC</i>	C11	S. Takeishi, H. Kudah, R. Shinohara, A. Tsukune, Y. Satoh, H. Miyazawa, H. Harada, and M. Yamada, "Stabilizing Dielectric Constants of Fluorine-Doped SiO ₂ Films by N ₂ O-Plasma Annealing," J. Electrochem. Soc., Vol. 143, No. 1, January 1996, Pages 381-384
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	A61	5,779,807	07-14-1998	Dornfest et al.	134	1.2	10-29-1996
	A62	5,780,163	07-14-1998	Camilletti et al.	428	446	06/05/1996
	A63	5,789,316	08-04-1998	Lu	438	637	03-10-1997
	A64	5,789,776	08-04-1998	Lancaster et al.	257	296	09-18-1996
	A65	5,790,365	08-04-1998	Shel	361	234	07-31-1996
	A66	5,801,098	09-01-1998	Fiordalice et al.	438	653	09-03-1996
	A67	5,817,579	10-06-1998	Ko et al.	438	740	04-09-1997
	A68	5,818,071	10-06-1998	Loboda et al.	257	77	02-02-1995
<i>V</i>	A69	5,827,785	10-27-1998	Bhan et al.	438	784	10-24-1996
<i>MCL</i>	A70	5,843,847	12-01-1998	Pu, et al.	438	723	04-29-1996

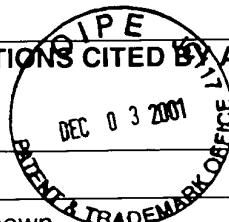
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<i>MCL</i>	B26	61000579	01-06-1986	JP (Abstract)	C23C	16/50	X	<input type="checkbox"/>

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	A72	5,869,396	02-09-1999	Pan et al.	438	647	07-15-1996
	A73	5,876,891	03-02-1999	Takimoto et al	430	71	05-26-1995
	A74	5,877,087	03-02-1999	Mosely, et al.	438	656	11-21-1995
	A75	5,899,720	05-04-1999	Mikagi	438	303	12-22-1995
	A76	5,950,083	09-07-1999	Inoue, et al.	438	233	09-25-1995
	A77	5,970,378	10-19-1999	Shue, et al.	438	656	07-23-1997
	A78	6,033,537	03-07-2000	Suguro	204	192.2	12-22-1997
<i>MFC</i>	A79	6,107,192	08-22-2000	Subrahmanyam et al.	438	637	12-30-1997
<i>MFC</i>	A80	6,125,859	10-03-2000	Kao et al.	134	1.1	07-11-1997

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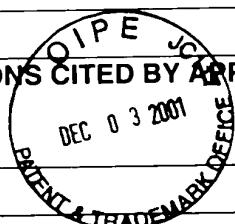
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	B28	62 158 859	07-14-1987	JP			X	
	B29	0 613 178 A2	02-22-1994	EPO	H 01 L	21/90	N/A	
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							YES	NO
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C16

C17

Examiner *Barbara M. Hart*Date Considered *9/20/01*

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.

U.S. Department of Commerce, Patent and Trademark Office (PTO Form 1449 modified)				Docket No. AMAT/4180/PDD/K PU1/JW	Serial No. 09/902,518		
INFORMATION DISCLOSURE STATEMENT BY APPLICANT				Applicant Huang, et al	Confirmation No.: 7428		
(Use several sheets if necessary)				Filing Date July 10, 2001	Group 2812 2824		
Examiner UNKNOWN							
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Foreign Patent Documents							
*Examiner Initial	Document Number	Date	Country	Class	Subclass	Translation	
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<i>BB</i>	B1 EP 0070 715 B1	03-18-1987	Europe	G 03 G 5	082	<input checked="" type="checkbox"/>	<input type="checkbox"/>
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	B3					<input type="checkbox"/>	<input type="checkbox"/>
OTHER ART							
*Examiner Initial	Including Author, Title, Date, Pertinent Pages, Etc.						
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	C2						
	C3						
Examiner <i>BB</i>				Date Considered <i>2/12/03</i>			
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U.S. Department of Commerce, Patent and Trademark Office		Docket No.	Serial No.
(PTO Form 1449 modified)		AMAT/4180	09/902,518
INFORMATION DISCLOSURE STATEMENT BY APPLICANT		Applicant	Confirmation No.:
DEC 24 2002 U.S. PATENT AND TRADEMARK OFFICE		Huang, et al.	7428
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	Examiner Michael Lebentritt	July 10, 2001	2824

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Foreign Patent Documents

*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation	
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	B2						<input type="checkbox"/>	<input type="checkbox"/>
	B3						<input type="checkbox"/>	<input type="checkbox"/>

OTHER ART

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	C1	
	C2	
	C3	

Examiner <i>ML</i>	Date Considered <i>2/6/03</i>
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